Attorney Docket No.: N1085-00256 [TSMC2003-0899]

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## FACSIMILE TRANSMITTAL SHEET

In re application of: Huang-Ming Chen et al. Examiner: Karla A. Moore

Serial No.: 10/765.808 Group Art Unit: 1792

Filed: 01/27/2004 Confirmation No.: 2454

FOR METHOD AND APPARATUS FOR BACKSIDE POLYMER REDUCTION IN DRY-

E I CH PROCESS

To: Examiner Karla A. Moore

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

FACSIMILE NUMBER: 571-273-1440

CONFIRMATION

TELEPHONE:

FROM: Mark J. Marcelli

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619.744.2243

DATE:

August 7, 2008

TOTAL # OF PAGES:

MESSAGE:

Pursuant to our telephone conversation of August 7, 2008, please call to discuss the proposed amendment to (rejected)

claim 8.

Mark J. Marcelli

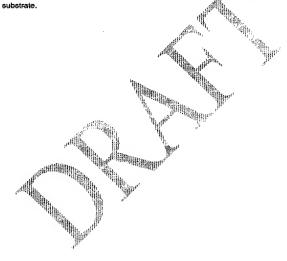
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1 8. (Currently Amended) A plasma etching apparatus comprising a chuck for retaining a substrate and a focus ring set, at least one of said chuck and said focus ring set formed of a material that includes oxygen therein such that said oxygen is released when an etching operation is carried out, said focus ring set including an upper focus ring that laterally surrounds said chuck and a lower focus ring disposed completely below said upper focus ring and directly underneath a peripheral portion of said chuck



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